A processing apparatus, which removes a processing agent adhered to a peripheral portion of a substrate on which the processing agent is coated, comprises a nozzle having a recess portion into which the peripheral portion of the substrate is inserted and for supplying a solvent to the peripheral portion of the substrate which has been inserted into the recess portion, a moving mechanism for moving the nozzle along the peripheral portion of the substrate, and rotating bodies for guiding the peripheral portion of the substrate to an inlet of the recess portion of the nozzle, whereby the processing agent on the peripheral portion of the substrate can be removed by the solvent which has been supplied to the peripheral portion of the substrate.

15 Claims, 10 Drawing Sheets